## Chapter 4

## New Technology in High Yield Pulping

## 4.1 General Description of High Yield Pulping

(1)Varieties of high yield pulp yield (on wood)%

Mechanical pulp>90Chemimechanical pulp80~92Semichemical pulp65~80High yield chemical pulp50~65

#### (2) Significance of developing high yield pulp

- Fully and reasonably utilize fibrous materials
- Reduce production cost
- Meet the property requirement of some products
- Decrease the pollution of pulping spent liquor

(3) Developing tendency of high yield pulping High yield High strength High brightness Low energy consumption Low pollution

#### (4) Technical terms

SGW -- Stone Groundwood **PGW -- Pressurized Groundwood PGW-S -- Super Pressurized Groundwood** TGW -- Thermogroundwood CGP -- Chemical Groundwood Pulp FGP -- Fine Groundwood Pulp **RMP** -- Refiner Mechanical Pulp TMP -- Thermo-Mechanical Pulp

CMP -- Chemi-Mechanical Pulp CTMP -- Chemi-Thermo-Mechanical Pulp **APMP -- Alkaline Peroxide Mechanical Pulp SCMP -- Sulfonated Chemimechanical Pulp BioMP** -- Bio-Mechanical Pulp SEP -- Steam Explosion Pulp **EMP -- Extruder Mechanical Pulp** SCP -- Semi-Chemical Pulp NSSC -- Neutral Sulfite Semi-Chemical Pulp ASSC -- Alkaline Sulfite Semi-Chemical Pulp

(5) Main characters of Mechanical pulp High opacity and light scattering coefficient Excellent printability (ink absorption) Good smoothness due to high content of fine High bulk which results in good stiffness of paper and paper board Good formation and dimension stability

# (6) Main uses of mechanical and chemimechanical pulps

#### Newsprint

- As a furnish of printing and writing paper
- As a furnish of supercalendering paper (SC) and light weight coated paper (LWC)
- As a furnish of paperboard
- Tissue and fluff pulp

## 4.2 Improvement of Stone Groundwood – PGW and PGW-S (1)Comparison of technological parameters of SGW, PGW and PGW-S

	SGW	PGW	PGW-S	
Linear speed of pulpstone m/s	17~24	28	28	
Grinding pressure KPa	Atmosphere	250	450	
Temp. of shower water $^{\circ}\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!\!$	60~70	105	140	
Temp. of pulp °C	75~85	109	139	

# (2) Comparison of specific energy consumption of PGW, PGW-S and TMP

		PGW-S	TMP
Grinding/refining KWh/t	1065	1030	1490
Reject refining KWh/t	95	110	130
Post refining KWh/t	_	_	15
Total KWh/t	1060	1140	1635
*65ml CSF			

#### (3) Comparison of pulp property of PGW, PGW-S and TMP

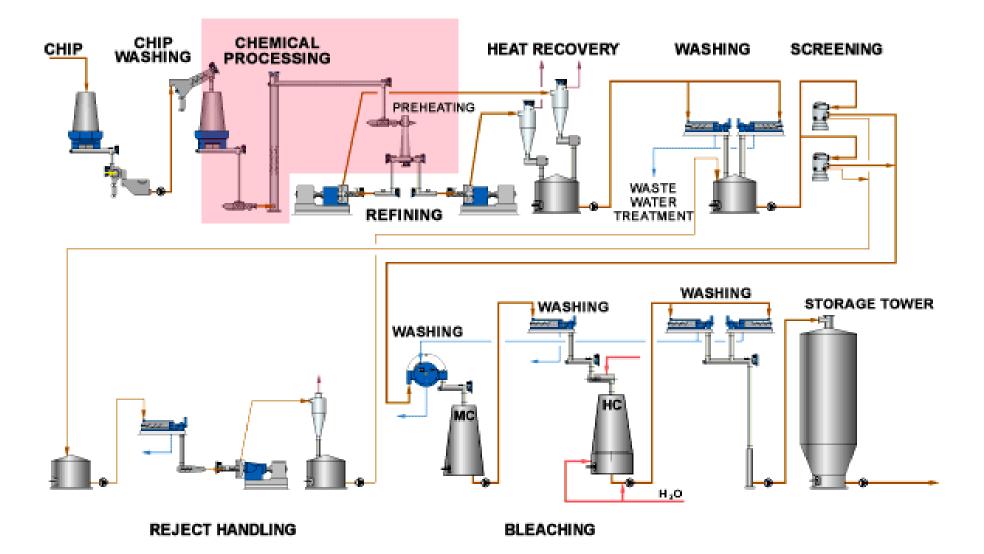
		PGW	PGW-S	TMP	
CSF (ml)		112	112	112	
Reject %		2.74	4.25	0.18	
Classification					
	R28 %	28.3	32.9	33.4	
	P200 %	30.3	28.8	28.1	
Tensile index	Nm/g	30.1	31.6	29.2	
Tear index	$mN \cdot m^2/g$	5.1	5.6	6.1	
Burst index	<b>kPa •</b> m <sup>2</sup> /g	1.7	2.1	2.3	
Light scattering co	oefficient m <sup>2</sup> /Kg	63.0	60.8	54.4	
Brightness	%ISO	64.0	59.7	59.4	
Density	kg/m <sup>3</sup>	350	354	377	

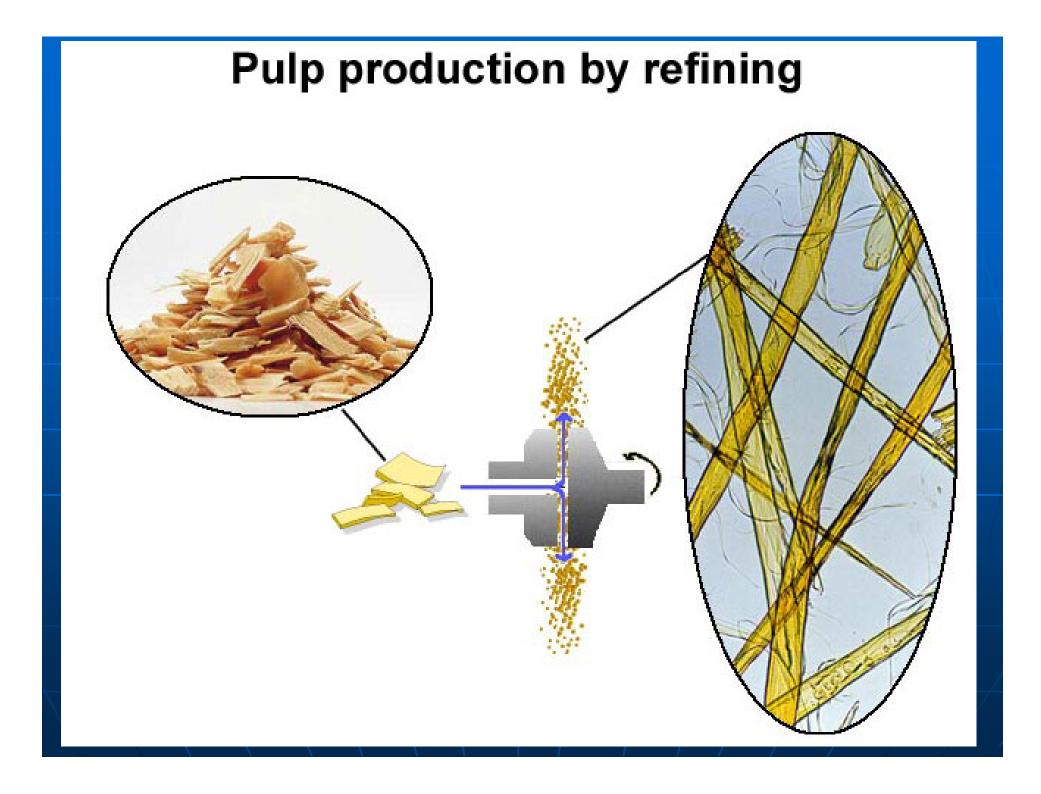
#### (4) Summary

- The energy consumption of PGW-S is similar to that of PGW, but much lower than that of TMP.
- The long fiber content of PGW-S is higher than that of PGW, and similar to that of TMP.
- The strength of PGW-S is much higher than that of PGW, the tensile and burst strength are close to TMP.

Light scattering coefficient of PGW-S is lower than that of PGW, but is much higher than that of TMP The brightness of PGW-S is similar to that of TMP, but the bleachability is much better than that of TMP The linting phenomena of stone groundwood are obviously less than that of TMP

#### **CTMP PROCESS DIAGRAM**





## 4.3 Improvement of TMP Technology –RTS TMP

**RTS Refining Technology** R-residence time T-temperature S-speed **Optimized technology** -short residence time -elevated temperature -high speed Objective of the modified technology increase selectively the temperature of secondary wall, but does not increase the temperature of middle lamella.

#### Comparison of TMP and RTS-TMP for newsprint

		TMP	<b>RTS-TMP</b>	
CSF ml		90	90	
Specific energy co	onsumption KWh/t	2198	1878	
Bulk cm <sup>3</sup> /g		2.38	2.38	
Burst index	$kPa \cdot m^2/g$	2.8	2.90	
Tear index	$mN \cdot m^2/g$	9.5	9.5	
Tensile index	Nm/g	46.6	47.2	
Tensile energy ab	sorption J/m <sup>2</sup>	47.1	49.7	
Shive	%	0.2	0.13	
Opacity	%	93.5	93.4	
Light scattering c	oefficient m <sup>2</sup> /Kg	55.9	58.2	
Brightness	%ISO	59.8	61.5	

#### Advantages of RTS-TMP compared with TMP

- Less energy consumption
- Slightly higher strength at the same CSF
- Much less shive
- Higher light scattering coefficient
- Higher brightness

### 4.4 Improvement of CMP-APMP&PRC-APMP

- APMP——a revolution in high yield pulping
- (1) Process description
- Two stages of impressafining (with impressafiner)
- Two stages of impregnation
- Two stages of atmospheric refining

(2)Chemicals used in APMP First stage: small amount or residual NaOH and H<sub>2</sub>O<sub>2</sub>, DTPA Second stage: NaOH H<sub>2</sub>O<sub>2</sub> DTPA (3) Advantages of APMP
 The pulp requires no additional bleaching after refining, the cost of building a plant can be reduced by 25% or more.

The impressafiner can squeeze out high levels of resins and water soluble materials from the chips Simple atmospheric refiners can be used, thus eliminating the need for extensive steaming systems The use of more caustic on the chips prior to refining reduces the energy consumption up to 40% Since the process does not use sulfite, the effluent from the plant will be easier to treat

Improvement of APMP—PRC-APMP P—Preconditioning RC—Refiner chemical APMP—Alkaline peroxide mechanical pulp

## 4.5 Latency and Delatency of High Yield Pulps

- (1) Reasons of generating latency
- High consistency
- High temperature soften the fiber
- Fiber torsion and curling, as temperature lowers out of refiner, the fibers keep the situation of torsion and curling

(2) Delatency
Higher temperature
Lower consistency
Stirring a certain time

70~90℃ 2%~4% 30min (3) Maximum changes observed after delatency
Shive content -75%
CSF -(100~150)ml
Tensile index +(30%~100%)
Tear index +15%

## 4.6 Comparison of several high yield pulps

In general, for the same fibrous material Yield: SGW>RMP>TMP>CTMP>CMP Strength: SGW<RMP<TMP<CTMP<CMP **Brightness:** TMP<PGW<SGW Brightness of CTMP and CMP depends on the chemicals and technological conditions **Opacity:** SGW>PGW>RMP>TMP>CTMP>CMP Refining energy (at the same CSF): PGW<SGW<RMP<TMP<CTMP